

Form PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		ATTY. DOCKET NO. SERIAL NO. APPLICANT FILING DATE GROUP				
U.S. PATENT DOCUMENTS						
Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA					
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	AJ					
	AK					
	AL					
FOREIGN PATENT DOCUMENTS						
	Document Number	Date	Country	Class	Subclass	Translation
						Yes No
	AM					
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)						
	AN		ARMAS, B., et al., "Chemical Vapor Deposition Of Si ₃ N ₄ and AlN on Carbon Fibers", <u>Chemical Vapor Deposition 1987</u> , The Electrochemical Society, Inc., Proceedings Vol 87-8, pp. 1060-69 (1987)			
	AO		SUZUKI, M., et al., "CVD Of Polycrystalline Aluminum Nitride", <u>Chemical Vapor Deposition 1987</u> , The Electrochemical Society, Inc., Proceedings Vol 87-8, pp. 1089-97 (1987)			
	AP		KOBAYASHI, N., et al., <u>Improved 2DEG Mobility In Selectively Doped GaAs/N-AlGaAs Grown by MOCVD Using Triethyl Organometallic Compounds</u> , Musashino Elect. Comm. Lab., Nippon Tel & Telegraph, Japan, 2 Pages, (9/10/1984)			
	AQ		PIERSON, Hugh O., <u>Handbook Of Chemical Vapor Deposition (CVD)</u> , Noyes Publications, N.J., pp. 216-219 (undated)			
	AR		<u>CVD Of Nonmetals</u> , Editor: William S. Rees, Jr., pp. 301-307 (1996)			
	AS		C. Jimenez et al., <u>Preparation of aluminum nitride films by low pressure organometallic chemical vapor deposition</u> , 76-77 SURFACE AND COATINGS TECHNOLOGY 372-376 (1995).			
	AT		H. Liu et al., <u>The surface chemistry of aluminum nitride MOCVD on alumina using trimethylaluminum and ammonia as precursors</u> , 320 SURFACE SCIENCE 145-160 (1994).			
	EXAMINER 		DATE CONSIDERED 9/24/02			
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Sheet 1 of 2

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U.S. PATENT DOCUMENTS

Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
yzh	AA	5,656,113	08/97	IKEDA ET AL.			
	AB	5,709,928	01/98	IKEDA ET AL.			
	AC	5,605,858	02/97	NISHIOKA ET AL.			
	AD	5,687,112	11/97	OVSHINSKY			
	AE	5,767,578	06/98	CHANG ET AL.			
	AF	5,773,882	06/98	IWASAKI			
	AG	5,783,483	07/98	GARDNER			
	AH	5,783,716	07/98	BAUM ET AL.			
	AI	5,786,635	07/98	ALCOE ET AL.			
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	AL	5,183,684	02/02/93	Carpenter			
	AM	5,356,608	10/18/94	Gebhardt			
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	AO	5,599,732	02/04/97	Razeghi			
	AP	5,650,361	07/22/97	Radhakrishnan			
ga	AQ	09/191,294	11/98	BRENDA D. KRAUS ET AL.			11-13-98
	AR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
yzh	AS	JP401230779A	09/14/89	Hayashi et al.				

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